

09/972,428

SHEET 11 of 12

INFORMATION DISCLOSURE CITATION PTO-1449		Atty. Docket No.	Serial No.
		NMTI 1002-4	09/972,428-3974
		Applicant	
		PIERRAT, Christophe	
		Filing Date	Group
		10/5/2001	2824 Not Yet Assigned
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)			
EXAMINER'S INITIALS	CITATION		
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JSR	Palmer, S., et al., "Dual Mask Model-Based Proximity Correction for High Performance 0.10um CMOS Process", The 44th International Conference on Electron, Ion and Photon Beam Technology and Nanofabrication Abstracts, pp. 18-19, May 30-June 24, 1999.		

EXAMINER:

J. Ruggles

Date Considered:

5/8/03

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP § 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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